

ABSTRACT OF THE DISCLOSURE

An apparatus is used for manufacturing semiconductor device, and the apparatus is not required to be installed in a clean room and is capable of processing
5 semiconductor wafers in a clean atmosphere without exposure to external environments. The apparatus comprises an enclosing structure defining a closed space isolated from an external environment, a purifying system for keeping the closed space clean, a processing device disposed in the
10 closed space for processing a semiconductor wafer, and a pressure elevating device for keeping an internal pressure high in the closed space so as to be higher than a pressure in the external environment.